

SYSTEM AND METHOD FOR CUSTOM-POLARIZED
PHOTOLITHOGRAPHY ILLUMINATION

ABSTRACT

5 In one embodiment, a system for custom-polarized photolithography illumination includes an illuminator operable to generate an illumination pattern of light, a polarizer unit operable to variably polarize the light, and a mask pattern defining photolithographic pattern features in two dimensions. The mask pattern is associated with a mask capable of transmitting at least a portion of the variably polarized light through the mask pattern.